## Han-Bo-Ram Lee

## List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

119<br/>papers5,191<br/>citations37<br/>h-index69<br/>g-index134<br/>ext. papers5,744<br/>ext. citations6.9<br/>avg, IF5.82<br/>L-index

#	Paper	IF	Citations
119	Icephobic Coating through a Self-Formed Superhydrophobic Surface Using a Polymer and Microsized Particles ACS Applied Materials & Interfaces, 2022,	9.5	3
118	Self-Formation of Superhydrophobic Surfaces through Interfacial Energy Engineering between Liquids and Particles. <i>Langmuir</i> , <b>2021</b> , 37, 5356-5363	4	5
117	Atomic Layer Modulation of Multicomponent Thin Films through Combination of Experimental and Theoretical Approaches. <i>Chemistry of Materials</i> , <b>2021</b> , 33, 4435-4444	9.6	2
116	Interfacial reactions and mechanical properties of transient liquid-phase bonding joints in Cu/Sn/Ni(P) and Ni/Sn/(OSP)Cu structures for power modules. <i>Journal of Materials Science: Materials in Electronics</i> , <b>2021</b> , 32, 3324-3333	2.1	О
115	Toward Enhanced Humidity Stability of Triboelectric Mechanical Sensors via Atomic Layer Deposition. <i>Nanomaterials</i> , <b>2021</b> , 11,	5.4	2
114	Evaluation of silicon tetrahalide precursors for low-temperature thermal atomic layer deposition of silicon nitride. <i>Applied Surface Science</i> , <b>2021</b> , 565, 150603	6.7	2
113	Dataset for TiN Thin Films Prepared by Plasma-Enhanced Atomic Layer Deposition Using Tetrakis(dimethylamino)titanium (TDMAT) and Titanium Tetrachloride (TiCl) Precursor. <i>Data in Brief</i> , <b>2020</b> , 31, 105777	1.2	2
112	Promoting lithium electrodeposition towards the bottom of 3-D copper meshes in lithium-based batteries. <i>Journal of Power Sources</i> , <b>2020</b> , 472, 228495	8.9	5
111	Preparation of a hydrophobic cerium oxide nanoparticle coating with polymer binder via a facile solution route. <i>Ceramics International</i> , <b>2020</b> , 46, 12209-12215	5.1	2
110	Tunable Color Coating of E-Textiles by Atomic Layer Deposition of Multilayer TiO/AlO Films. <i>Langmuir</i> , <b>2020</b> , 36, 2794-2801	4	12
109	Effects of Al Precursors on Deposition Selectivity of Atomic Layer Deposition of Al2O3 Using Ethanethiol Inhibitor. <i>Chemistry of Materials</i> , <b>2020</b> , 32, 8921-8929	9.6	15
108	Surface Energy Change of Atomic-Scale Metal Oxide Thin Films by Phase Transformation. <i>ACS Nano</i> , <b>2020</b> , 14, 676-687	16.7	5
107	Effect of molecular backbone structure on vapor phase coupling reaction between diiso(thio)cyanates with diamines, diols, and dithiols. <i>Progress in Organic Coatings</i> , <b>2020</b> , 140, 105509	4.8	2
106	Atomic level deposition to extend Moore law and beyond. <i>International Journal of Extreme Manufacturing</i> , <b>2020</b> , 2, 022002	7.9	22
105	Thermal atomic layer deposition of metallic Ru using H2O as a reactant. <i>Applied Surface Science</i> , <b>2019</b> , 488, 896-902	6.7	8
104	Moisture barrier properties of low-temperature atomic layer deposited Al2O3 using various oxidants. <i>Ceramics International</i> , <b>2019</b> , 45, 19105-19112	5.1	8
103	Analysis of Defect Recovery in Reduced Graphene Oxide and Its Application as a Heater for Self-Healing Polymers. <i>ACS Applied Materials &amp; Self-Healing Polymers</i> . <i>ACS Applied Materials &amp; Self-Healing Polymers</i> .	9.5	13

## (2017-2019)

102	Reaction Mechanism of Pt Atomic Layer Deposition on Various Textile Surfaces. <i>Chemistry of Materials</i> , <b>2019</b> , 31, 8995-9002	9.6	4
101	Interlayer-assisted atomic layer deposition of MgO as a magnetic tunneling junction insulators. <i>Journal of Alloys and Compounds</i> , <b>2018</b> , 747, 505-510	5.7	7
100	Circular Double-Patterning Lithography Using a Block Copolymer Template and Atomic Layer Deposition. <i>Advanced Materials Interfaces</i> , <b>2018</b> , 5, 1800054	4.6	8
99	Copper indium selenide water splitting photoanodes with artificially designed heterophasic blended structure and their high photoelectrochemical performances. <i>Nano Energy</i> , <b>2018</b> , 46, 1-10	17.1	5
98	Water-Erasable Memory Device for Security Applications Prepared by the Atomic Layer Deposition of GeO2. <i>Chemistry of Materials</i> , <b>2018</b> , 30, 830-840	9.6	5
97	Comparative study of the growth characteristics and electrical properties of atomic-layer-deposited HfO2 films obtained from metal halide and amide precursors. <i>Journal of Materials Chemistry C</i> , <b>2018</b> , 6, 7367-7376	7.1	23
96	Molecular oxidation of surface IIH3 during atomic layer deposition of Al2O3 with H2O, H2O2, and O3: A theoretical study. <i>Applied Surface Science</i> , <b>2018</b> , 457, 376-380	6.7	18
95	Amorphous TiO2/p-Si Heterojunction Photodiode Prepared by Low-Temperature Atomic Layer Deposition. <i>Nanoscience and Nanotechnology Letters</i> , <b>2018</b> , 10, 800-804	0.8	2
94	Surface Wettability of Nitrogen-Doped TiO2 Films Prepared by Atomic Layer Deposition Using NH4OH as the Doping Source. <i>Nanoscience and Nanotechnology Letters</i> , <b>2018</b> , 10, 779-783	0.8	1
93	Cobalt titanium nitride amorphous metal alloys by atomic layer deposition. <i>Journal of Alloys and Compounds</i> , <b>2018</b> , 737, 684-692	5.7	4
92	Area-Selective Atomic Layer Deposition Using Si Precursors as Inhibitors. <i>Chemistry of Materials</i> , <b>2018</b> , 30, 7603-7610	9.6	52
91	Atomic Layer Deposition: Circular Double-Patterning Lithography Using a Block Copolymer Template and Atomic Layer Deposition (Adv. Mater. Interfaces 16/2018). <i>Advanced Materials Interfaces</i> , <b>2018</b> , 5, 1870078	4.6	
90	Effect of h-BN coating on nucleate boiling heat transfer performance in pool boiling. <i>Experimental Thermal and Fluid Science</i> , <b>2018</b> , 98, 12-19	3	14
89	A composite layer of atomic-layer-deposited Al2O3 and graphene for flexible moisture barrier. <i>Carbon</i> , <b>2017</b> , 116, 553-561	10.4	40
88	Vapor phase synthesis of TaS2 nanocrystals with iodine as transport agent. <i>Japanese Journal of Applied Physics</i> , <b>2017</b> , 56, 045501	1.4	2
87	Distribution of oxygen functional groups of graphene oxide obtained from low-temperature atomic layer deposition of titanium oxide. <i>RSC Advances</i> , <b>2017</b> , 7, 13979-13984	3.7	32
86	Atomic layer deposition of 1D and 2D nickel nanostructures on graphite. <i>Nanotechnology</i> , <b>2017</b> , 28, 115	30 <sub>4</sub>	8
85	Nanoconfined Atomic Layer Deposition of TiO2/Pt Nanotubes: Toward Ultrasmall Highly Efficient Catalytic Nanorockets. <i>Advanced Functional Materials</i> , <b>2017</b> , 27, 1700598	15.6	46

84	Atomic Layer Deposition on 2D Materials. <i>Chemistry of Materials</i> , <b>2017</b> , 29, 3809-3826	9.6	119
83	Atomic layer deposition of Y-stabilized ZrO2 for advanced DRAM capacitors. <i>Journal of Alloys and Compounds</i> , <b>2017</b> , 722, 307-312	5.7	28
82	Growth mechanism of Co thin films formed by plasma-enhanced atomic layer deposition using NH3 as plasma reactant. <i>Current Applied Physics</i> , <b>2017</b> , 17, 333-338	2.6	10
81	Dual Role of Sb-Incorporated Buffer Layers for High Efficiency Cuprous Oxide Photocathodic Performance: Remarkably Enhanced Crystallinity and Effective Hole Transport. <i>ACS Sustainable Chemistry and Engineering</i> , <b>2017</b> , 5, 8213-8221	8.3	11
80	Conduction mechanism change with transport oxide layer thickness in oxide hetero-interface diode. <i>Applied Physics Letters</i> , <b>2017</b> , 111, 053506	3.4	4
79	Reaction Mechanism of Area-Selective Atomic Layer Deposition for AlO Nanopatterns. <i>ACS Applied Materials &amp; Amp; Interfaces</i> , <b>2017</b> , 9, 41607-41617	9.5	50
78	Uniform color coating of multilayered TiO2/Al2O3 films by atomic layer deposition <b>2017</b> , 14, 177-183		3
77	Photocatalytic Effect of Ag/TiO2 Nanotubes Fabricated Using 40 nm-Scale BCP Lithography. <i>Nanoscience and Nanotechnology Letters</i> , <b>2017</b> , 9, 50-55	0.8	4
76	Highly conductive and flexible fiber for textile electronics obtained by extremely low-temperature atomic layer deposition of Pt. <i>NPG Asia Materials</i> , <b>2016</b> , 8, e331-e331	10.3	41
75	Fabrication of 50 nm scale Pt nanostructures by block copolymer (BCP) and its characteristics of surface-enhanced Raman scattering (SERS). <i>RSC Advances</i> , <b>2016</b> , 6, 70756-70762	3.7	9
74	Complementary Unipolar WS2 Field-Effect Transistors Using Fermi-Level Depinning Layers. <i>Advanced Electronic Materials</i> , <b>2016</b> , 2, 1500278	6.4	22
73	Formation of Ni silicide from atomic layer deposited Ni. Current Applied Physics, 2016, 16, 720-725	2.6	4
72	Highly-conformal nanocrystalline molybdenum nitride thin films by atomic layer deposition as a diffusion barrier against Cu. <i>Journal of Alloys and Compounds</i> , <b>2016</b> , 663, 651-658	5.7	24
71	Plasma-enhanced atomic layer deposition of SnO2 thin films using SnCl4 and O2 plasma. <i>Materials Letters</i> , <b>2016</b> , 166, 163-166	3.3	17
70	Growth characteristics and electrical properties of SiO2 thin films prepared using plasma-enhanced atomic layer deposition and chemical vapor deposition with an aminosilane precursor. <i>Journal of Materials Science</i> , <b>2016</b> , 51, 5082-5091	4.3	23
69	Effects of Cl-Based Ligand Structures on Atomic Layer Deposited HfO2. <i>Journal of Physical Chemistry C</i> , <b>2016</b> , 120, 5958-5967	3.8	11
68	Wafer-scale, conformal and direct growth of MoS2 thin films by atomic layer deposition. <i>Applied Surface Science</i> , <b>2016</b> , 365, 160-165	6.7	96
67	Self-Limiting Layer Synthesis of Transition Metal Dichalcogenides. <i>Scientific Reports</i> , <b>2016</b> , 6, 18754	4.9	62

## (2015-2016)

66	Comparison of hydrogen sulfide gas and sulfur powder for synthesis of molybdenum disulfide nanosheets. <i>Current Applied Physics</i> , <b>2016</b> , 16, 691-695	2.6	12
65	High efficiency n-Si/p-Cu2O core-shell nanowires photodiode prepared by atomic layer deposition of Cu2O on well-ordered Si nanowires array. <i>Electronic Materials Letters</i> , <b>2016</b> , 12, 404-410	2.9	12
64	A controlled growth of WNx and WCx thin films prepared by atomic layer deposition. <i>Materials Letters</i> , <b>2016</b> , 168, 218-222	3.3	22
63	Area-selective chemical vapor deposition of Co for Cu capping layer. <i>Current Applied Physics</i> , <b>2016</b> , 16, 88-92	2.6	9
62	Effects of TaN Diffusion Barrier on Cu-Gate ZnO:N Thin-Film Transistors. <i>IEEE Electron Device Letters</i> , <b>2016</b> , 37, 599-602	4.4	4
61	A facile method for the selective decoration of graphene defects based on a galvanic displacement reaction. <i>NPG Asia Materials</i> , <b>2016</b> , 8, e262-e262	10.3	14
60	Very high frequency plasma reactant for atomic layer deposition. <i>Applied Surface Science</i> , <b>2016</b> , 387, 109-117	6.7	11
59	Real-time detection of chlorine gas using Ni/Si shell/core nanowires. <i>Nanoscale Research Letters</i> , <b>2015</b> , 10, 18	5	7
58	Reversible Liquid Adhesion Switching of Superamphiphobic Pd-Decorated Ag Dendrites via Gas-Induced Structural Changes. <i>Chemistry of Materials</i> , <b>2015</b> , 27, 4964-4971	9.6	23
57	Internal and external atomic steps in graphite exhibit dramatically different physical and chemical properties. <i>ACS Nano</i> , <b>2015</b> , 9, 3814-9	16.7	43
56	Formation of Continuous Pt Films on the Graphite Surface by Atomic Layer Deposition with Reactive O3. <i>Chemistry of Materials</i> , <b>2015</b> , 27, 6802-6809	9.6	24
55	Nucleation and Growth of the HfO2 Dielectric Layer for Graphene-Based Devices. <i>Chemistry of Materials</i> , <b>2015</b> , 27, 5868-5877	9.6	37
54	Hydrophobicity of Rare Earth Oxides Grown by Atomic Layer Deposition. <i>Chemistry of Materials</i> , <b>2015</b> , 27, 148-156	9.6	90
53	In situ surface cleaning on a Ge substrate using TMA and MgCp2 for HfO2-based gate oxides. <i>Journal of Materials Chemistry C</i> , <b>2015</b> , 3, 4852-4858	7.1	17
52	Improved Corrosion Resistance and Mechanical Properties of CrN Hard Coatings with an Atomic Layer Deposited Al2O3 Interlayer. <i>ACS Applied Materials &amp; Deposited Al2O3 Interlayer</i> . <i>ACS Applied Materials &amp; Deposited Al2O3 Interlayer</i> .	9.5	46
51	Plasma-enhanced atomic layer deposition of Co on metal surfaces. <i>Surface and Coatings Technology</i> , <b>2015</b> , 264, 60-65	4.4	7
50	One-step hydrothermal synthesis of graphene decorated V2O5 nanobelts for enhanced electrochemical energy storage. <i>Scientific Reports</i> , <b>2015</b> , 5, 8151	4.9	141
49	Growth of Atomic Layer Deposition Platinum on TiO2. <i>Journal of the Korean Institute of Surface Engineering</i> , <b>2015</b> , 48, 38-42		

48	Atomic Layer Deposition for Semiconductors <b>2014</b> ,		55
47	Selective metal deposition at graphene line defects by atomic layer deposition. <i>Nature Communications</i> , <b>2014</b> , 5, 4781	17.4	196
46	Effect of O3 on Growth of Pt by Atomic Layer Deposition. <i>Journal of Physical Chemistry C</i> , <b>2014</b> , 118, 12325-12332	3.8	36
45	Contact resistance reduction using Fermi level de-pinning layer for MoS2 FETs <b>2014</b> ,		14
44	Vapor transport deposition and epitaxy of orthorhombic SnS on glass and NaCl substrates. <i>Applied Physics Letters</i> , <b>2013</b> , 103, 052105	3.4	40
43	Self-assembly based plasmonic arrays tuned by atomic layer deposition for extreme visible light absorption. <i>Nano Letters</i> , <b>2013</b> , 13, 3352-7	11.5	104
42	Plasma-enhanced atomic layer deposition of Co using Co(MeCp)2 precursor. <i>Journal of Energy Chemistry</i> , <b>2013</b> , 22, 403-407	12	19
41	Growth of Pt nanowires by atomic layer deposition on highly ordered pyrolytic graphite. <i>Nano Letters</i> , <b>2013</b> , 13, 457-63	11.5	78
40	Ru nanodot synthesis using CO2 supercritical fluid deposition. <i>Journal of Physics and Chemistry of Solids</i> , <b>2013</b> , 74, 664-667	3.9	4
39	Highly sensitive, patternable organic films at the nanoscale made by bottom-up assembly. <i>ACS Applied Materials &amp; Discourse (Materials &amp; Discourse)</i> , 1, 3691-6	9.5	14
38	Flexible wireless temperature sensors based on Ni microparticle-filled binary polymer composites. <i>Advanced Materials</i> , <b>2013</b> , 25, 850-5	24	240
37	Initial Stage Growth during Plasma-Enhanced Atomic Layer Deposition of Cobalt. <i>Chemical Vapor Deposition</i> , <b>2012</b> , 18, 41-45		18
36	The low temperature atomic layer deposition of ruthenium and the effect of oxygen exposure. Journal of Materials Chemistry, <b>2012</b> , 22, 25154		29
35	Nucleation-Controlled Growth of Nanoparticles by Atomic Layer Deposition. <i>Chemistry of Materials</i> , <b>2012</b> , 24, 4051-4059	9.6	47
34	Microstructure-Dependent Nucleation in Atomic Layer Deposition of Pt on TiO2. <i>Chemistry of Materials</i> , <b>2012</b> , 24, 279-286	9.6	62
33	Nanopatterning by Area-Selective Atomic Layer Deposition <b>2012</b> , 193-225		29
32	Active MnOx Electrocatalysts Prepared by Atomic Layer Deposition for Oxygen Evolution and Oxygen Reduction Reactions. <i>Advanced Energy Materials</i> , <b>2012</b> , 2, 1269-1277	21.8	269
31	Fluorine functionalization of epitaxial graphene for uniform deposition of thin high-ldielectrics. <i>Carbon</i> , <b>2012</b> , 50, 2307-2314	10.4	62

30	Silicidation of Co/Si Core Shell Nanowires. <i>Journal of the Electrochemical Society</i> , <b>2012</b> , 159, K146-K151	3.9	6
29	Seeding atomic layer deposition of high-k dielectrics on epitaxial graphene with organic self-assembled monolayers. <i>ACS Nano</i> , <b>2011</b> , 5, 5223-32	16.7	149
28	Effects of self-assembled monolayers on solid-state CdS quantum dot sensitized solar cells. <i>ACS Nano</i> , <b>2011</b> , 5, 1495-504	16.7	84
27	Atomic Layer Deposition of CdS Quantum Dots for Solid-State Quantum Dot Sensitized Solar Cells. <i>Advanced Energy Materials</i> , <b>2011</b> , 1, 1169-1175	21.8	69
26	Atomic Layer Deposition of Ni Thin Films and Application to Area-Selective Deposition. <i>Journal of the Electrochemical Society</i> , <b>2011</b> , 158, D1	3.9	72
25	Atomic Layer Deposition of Co Using N2H2 Plasma as a Reactant. <i>Journal of the Electrochemical Society</i> , <b>2011</b> , 158, H1179	3.9	27
24	Supercritical Fluid Deposition of SiO2Thin Films: Growth Characteristics and Film Properties. Journal of the Electrochemical Society, <b>2011</b> , 159, D46-D49	3.9	5
23	In-situ synchrotron X-ray scattering study of thin film growth by atomic layer deposition. <i>Journal of Nanoscience and Nanotechnology</i> , <b>2011</b> , 11, 1577-80	1.3	5
22	2011,		41
21	Plasma-Enhanced Atomic Layer Deposition of Ni. <i>Japanese Journal of Applied Physics</i> , <b>2010</b> , 49, 05FA11	1.4	23
20	High Quality Area-Selective Atomic Layer Deposition Co Using Ammonia Gas as a Reactant. <i>Journal of the Electrochemical Society</i> , <b>2010</b> , 157, D10	3.9	60
19	Plasma-Enhanced Atomic Layer Deposition of Cobalt Using Cyclopentadienyl Isopropyl Acetamidinato-Cobalt as a Precursor. <i>Japanese Journal of Applied Physics</i> , <b>2010</b> , 49, 05FA10	1.4	25
18	Deposition of Ultrathin Polythiourea Films by Molecular Layer Deposition. <i>Chemistry of Materials</i> , <b>2010</b> , 22, 5563-5569	9.6	66
17	Area Selective Atomic Layer Deposition by Microcontact Printing with a Water-Soluble Polymer. Journal of the Electrochemical Society, <b>2010</b> , 157, D600	3.9	23
16	Self-formation of dielectric layer containing CoSi2 nanocrystals by plasma-enhanced atomic layer deposition. <i>Journal of Crystal Growth</i> , <b>2010</b> , 312, 2215-2219	1.6	15
15	Atomic layer deposited aluminum oxide films on graphite and graphene studied by XPS and AFM. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , <b>2010</b> , 7, 398-401		39
14	?The Degradation of Deposition Blocking Layer during Area Selective Plasma Enhanced Atomic Layer Deposition of Cobalt. <i>Journal of the Korean Physical Society</i> , <b>2010</b> , 56, 104-107	0.6	22
13	Supercritical Fluid Deposition of Conformal SrTiO[sub 3] Films with Composition Uniformity in Nanocontact Holes. <i>Electrochemical and Solid-State Letters</i> , <b>2009</b> , 12, D45		12

12	Applications of atomic layer deposition to nanofabrication and emerging nanodevices. <i>Thin Solid Films</i> , <b>2009</b> , 517, 2563-2580	2.2	475
11	Area Selective Atomic Layer Deposition of Cobalt Thin Films. <i>ECS Transactions</i> , <b>2009</b> , 16, 219-225	1	31
10	Utilization of a buffered dielectric to achieve high field-effect carrier mobility in graphene transistors. <i>Nano Letters</i> , <b>2009</b> , 9, 4474-8	11.5	310
9	Cobalt and nickel atomic layer depositions for contact applications 2009,		2
8	Atomic layer deposition of metal oxides on pristine and functionalized graphene. <i>Journal of the American Chemical Society</i> , <b>2008</b> , 130, 8152-3	16.4	562
7	Spontaneous formation of vertical magnetic-metal-nanorod arrays during plasma-enhanced atomic layer deposition. <i>Small</i> , <b>2008</b> , 4, 2247-54	11	31
6	Thermal and plasma enhanced atomic layer deposition ruthenium and electrical characterization as a metal electrode. <i>Microelectronic Engineering</i> , <b>2008</b> , 85, 39-44	2.5	80
5	Stress dependence of growth mode change of epitaxial layered cobaltite ENa0.7CoO2. <i>Applied Surface Science</i> , <b>2007</b> , 254, 436-440	6.7	4
4	High quality epitaxial CoSi2 using plasma nitridation-mediated epitaxy: The effects of the capping layer. <i>Journal of Applied Physics</i> , <b>2007</b> , 102, 094509	2.5	3
3	Nitride mediated epitaxy of CoSi2 through self-interlayer-formation of plasma-enhanced atomic layer deposition Co. <i>Applied Physics Letters</i> , <b>2007</b> , 90, 213509	3.4	25
2	The Structure of BC3N Tubular Nanofiber Synthesized by Using PECVD. <i>Journal of the Korean Physical Society</i> , <b>2007</b> , 51, 125	0.6	4
1	High-Quality Cobalt Thin Films by Plasma-Enhanced Atomic Layer Deposition. <i>Electrochemical and Solid-State Letters</i> , <b>2006</b> , 9, G323		82